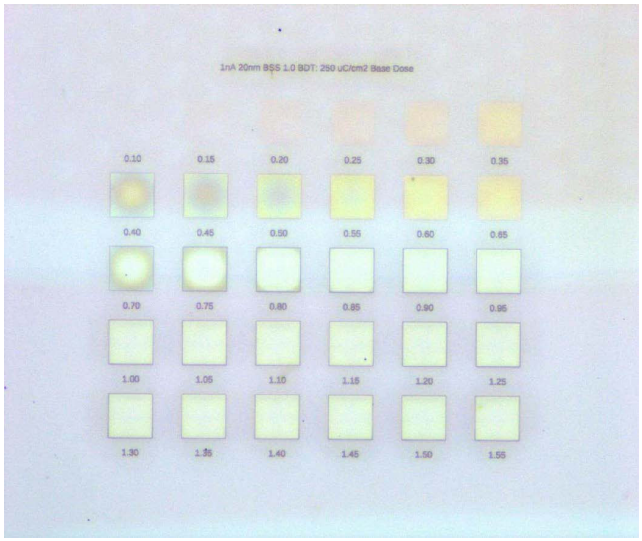
DisChem
CHEMISTRY FOR ADVANCED LITHOGRAPHY

ANTI-CHARGING

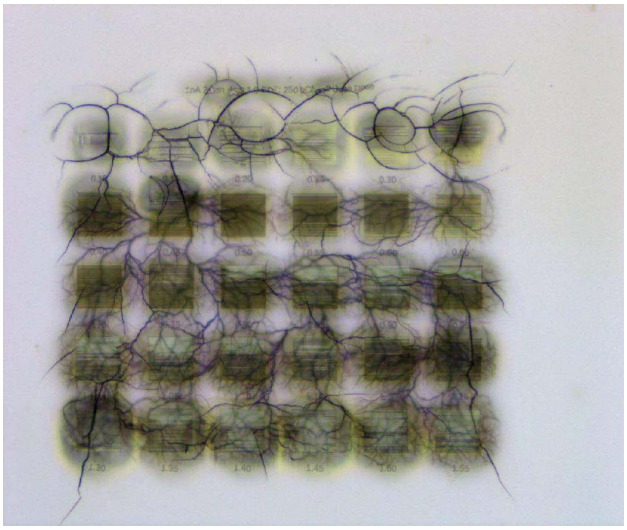
DisCharge

Charge Dissipation / Anti-Charging Agent

- Improved shape fidelity and positional accuracy for EBL resist patterning on insulated substrates such as fused silica, quartz, glass, PDMS, etc.
- Water based with excellent wetting properties. Spin coat application provides conductive film for successful patterning. Available in three concentrations for wide process window.
- Suitable for non-destructive SEM imaging of non-conductive materials.
- Easy residue free removal with water or IPA.
- Competitively priced. Ideal for both research and industrial applications.
- Two-year shelf life at room temperature. Highly stable permanently charged non-polymer formulation. Ready to use, no filtration required.



WITH DisCharge: no charge accumulation resulting in expected image with no harm to PDMS layer



Without DisCharge: charge accumulation and sudden charge dissipation caused by exceeding the dielectric breakdown strength of PDMS to the Si substrate resulting in significant cracking of the resist.

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